

# Source Power and Etendue Requirements

Throughput may be increased continuously, though throughput of 100 Wafer/hr will be attained using light source of 115W at the beginning of mass production of devices using EUVL. For this reason, higher source power may be needed.

EUVL should be applied over two or more technology nodes. To achieve this purpose, Larger NA is needed.

Solution 1: Narrower slit width  
Smaller etendue will be needed.

Solution 2: Increased mirror number  
Higher power will be needed.

